

### **Remarks**

The amendments are supported by the original claims and the specification at page 7, line 9 to page 8, line 1. Applicants submit that the amendment does not add any new matter to the disclosure.

The invention centers on novel resist compositions which involve use of a combination a dissolution inhibiting acid generator and a solubility promoting (acidic group-functionalized) acid generator. These resist compositions are advantageously suitable for low energy imaging (e.g., EPL, EUV, or soft x-ray).

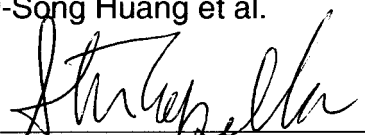
Hayase et al. (US 5580702 and US 5403695), Kimura (US 5679497) and Endo et al. (US 6949329) each disclose resist compositions where various combinations of acid generators are selected primarily on the basis of the quality of acid they produce or their sensitivity to specific forms of imaging radiation. None of the references discloses or suggests the combination of acid generators where one acid generator itself inhibits dissolution and the other acid generator itself is acidic-group functionalized. None of the references discloses or suggests the use of combinations of a dissolution inhibiting acid generator with dimethyl (3, 5-dimethyl)-4-hydroxyphenyl sulfonium perfluorobutane sulfonate.

For the above reasons, applicants respectfully submit that the claims are now allowable over the prior art of record and that the application is in condition for allowance. Such allowance is earnestly and respectfully solicited.

Respectfully submitted,

Wu-Song Huang et al.

By



Steven Capella, Attorney

Reg. No. 33,086

Telephone: 845-894-3669